

# Notice of Allowability

Application No.

10/510,916

Examiner

Stephen Rosasco

Applicant(s)

ISHIBASHI ET AL.

Art Unit

1795

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to Election 1/14/08.
2. ☒ The allowed claim(s) is/are 1-23 and 30-44.
3. ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
  - a) ☒ All    b) ☐ Some\*    c) ☐ None    of the:
    1. ☒ Certified copies of the priority documents have been received.
    2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
    3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

\* Certified copies not received: \_\_\_\_\_.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.

**THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.**

4. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
  5. ☐ CORRECTED DRAWINGS (as "replacement sheets") must be submitted.
    - (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached
      - 1) ☐ hereto or 2) ☐ to Paper No./Mail Date \_\_\_\_\_.
    - (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date \_\_\_\_\_.
- Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
6. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

## Attachment(s)

- |  |  |
|--|--|
| 1. <input checked="" type="checkbox"/> Notice of References Cited (PTO-892)  | 5. <input type="checkbox"/> Notice of Informal Patent Application                      |
| 2. <input type="checkbox"/> Notice of Draftperson's Patent Drawing Review (PTO-948)  | 6. <input type="checkbox"/> Interview Summary (PTO-413),<br>Paper No./Mail Date _____. |
| 3. <input checked="" type="checkbox"/> Information Disclosure Statements (PTO/SB/08),<br>Paper No./Mail Date <u>See Continuation Sheet</u> | 7. <input checked="" type="checkbox"/> Examiner's Amendment/Comment                    |
| 4. <input type="checkbox"/> Examiner's Comment Regarding Requirement for Deposit<br>of Biological Material                                 | 8. <input checked="" type="checkbox"/> Examiner's Statement of Reasons for Allowance   |
|  | 9. <input type="checkbox"/> Other _____.   |

Continuation of Attachment(s) 3. Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date: 6/9/05, 9/13/06, 12/5/07.

### Examiner's Amendment

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Cancel claims 24-29.

Authorization for this examiner's amendment was given by virtue of the election without traverse to the restriction requirement.

Applicant's election without traverse of Group I (claims 1-23 and 30-44) in the reply filed on 1/14/08 is acknowledged.

### ALLOWANCE

The following is an examiner's statement of reasons for allowance: the claimed invention is distinguished over the prior art of record in that the prior art does not teach the specific composition of the absorber layer of - a reflective mask and a reflective mask blank comprising a substrate on which a reflective layer for reflecting exposure light in a short-wavelength region including an extreme ultraviolet region and an absorber layer for absorbing the exposure light are successively formed, the absorber layer having an at least two-layer structure including as a lower layer an exposure light absorbing layer comprising an absorber for the exposure light and as an upper layer a low-reflectivity layer comprising an absorber for inspection light used in inspection of a mask pattern, the upper layer being

farther from the substrate than the lower layer, wherein the upper layer is made of a material containing tantalum (Ta), boron (B), and nitrogen (N), the content of B being 5 at % to 30 at %, the ratio of Ta and N (Ta:N) falling within a range of 8:1 to 2:7.

The applicant discusses the limitations of the prior art in that the reflectivity of the absorber layer can be decreased to enable mask pattern inspection to be accurately and quickly carried out by functionally separating an absorber layer on a surface of an existing mask into a layer for absorbing exposure light and a layer having a low reflectivity for a mask pattern inspection wavelength and by laminating these layers, a sufficient contrast is obtained upon pattern inspection.

Wasson et al. (6,939,650) teach a mask comprising a transparent substrate; a patterned absorbing layer; a buffer layer located between the transparent substrate and the patterned absorbing layer, the buffer layer having a pattern translated from the patterned absorbing layer; wherein the absorbing layer includes at least one of tantalum silicon nitride, tantalum silicon oxide, tantalum boron nitride, tantalum nitride, and tantalum oxide; wherein inspecting the absorbing layer of the mask after the etching the absorbing layer and before the etching the buffer layer.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

*Conclusion*

Any inquiry concerning this communication or earlier communications from the Examiner should be directed to Stephen Rosasco whose telephone number is (571) 272-1389. The Examiner can normally be reached Monday-Friday, from 8:00 AM to 4:30 PM. The Examiner's supervisor, Mark Huff, can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

A handwritten signature in black ink, appearing to read 'S. Rosasco', with a stylized, sweeping initial 'S'.

S. Rosasco  
Primary Examiner  
Art Unit 1756

S. Rosasco  
01/28/08